Docket No.: 21302/0203830-US0 (PATENT)

December 8, 2008

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Euijoon Yoon et al.

Application No.: 10/563,854 Confirmation No.: 3828

Filed: June 9, 2006 Art Unit: 2823

For: GROWTH METHOD FOR NITRIDE

SEMICONDUCTOR EPITAXIAL LAYERS

Examiner: Maldonado, J. J.

AMENDMENT ACCOMPANYING REQUEST FOR CONTINUED EXAMINATION

MS RCE Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

INTRODUCTORY COMMENTS

This Amendment is submitted concurrently with a Request for Continued Examination (RCE) for the above-identified application.

In response to the Final Office Action dated July 8, 2008 and the mailing of an Advisory Action on October 28, 2008, please amend the above-identified U.S. patent application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 6 of this paper.